Northern California Chapter of the American Vacuum Society (NCCAVS) CMP User Group (CMPUG) 2024 SPRING SYMPOSIUM – AGENDA

Meeting Date: Thursday, May 2, 2024
Meeting Time: 11:30 am – 5:00 pm (Central Time)
Offsite Dinner: 5:00 pm – 9:00pm
Location: The University of Texas at Austin
Thompson Conference Center, Room: Auditorium #1.110
2405 Robert Dedman Dr., Austin, TX 78712

Co-Chairs:
Michael Pevny, 3M, mpevny@mmm.com
Michael Wedlake, michael.wedlake@gmail.com

AGENDA

11:30 am – Welcome and Acknowledgment of Sponsors; Symposium Co-Chairs Michael Pevny, 3M, and Michael Wedlake and U.S. CMPUG Chair Bob Roberts, X-Trinsic

11:40 am – Semi Americas Outlook Growth Opportunities (Keynote), Dr. Daniel Muscat, EMD Electronics

12:05 pm – European CMP Users Group Activities and ICPT2024, Dr. Knut Gottfried and Imme Ellebrecht, Fraunhofer ENAS, ErzM-Technologies, European CMP & WET User Group (Remote)

12:25 pm – Advanced Semiconductor Technology Roadmaps and Implications to CMP Materials, Dr. Karey Holland and Diane Scott, Techcet

12:45 pm – Tailoring Molecular Structure for Defect Activated p-CMP Cleaning Processes, Dr Jason Keleher, Lewis University (Remote)

1:10 pm – Trends in CMP and Impact on Consumables, Mike Corbett, Linx Consulting

1:30 pm – Announcements/Coffee Break

1:45 pm – Controlling the Coefficient of Friction in CMP, Len Borucki, Araca (ret.)

2:10 pm – Environmentally Friendly Amino Acid-Based Polishing Slurry with Reduced Galvanic Corrosion at Copper/Cobalt Interface for Advanced Cu Interconnect Applications, Thi Thuy Hoang Tran (Presenter, Senior PhD Student), Elizabeth J. Podlaha, and Jihoon Seo, Clarkson University

2:35 pm – SiC CMP – A Process Perspective, Rob Rhoades, X-Trinsic

3:00 pm – Electrochemical Innovation for Sustainable Copper Management in CuCMP Wastewater, Dr. Cameron Lippert, ElectraMet

3:25 pm – The Value of CMP Education, Dr. Andrew Mansson, Samsung Austin Semiconductor

3:45 pm – Reducing CMP Process Mass Intensity, Steve Benner, Confluense, LLC

4:10 pm – Total Holographic Characterization of large particle contaminants in CMP slurries, Laura Philips, Spheryx (Remote)

4:35 pm – Pad-Level Spent Slurry Extraction During Polish, Dr. Ara Philipposian, Araca Inc

5:00 pm – Closing Remarks, Co-chairs Michael Pevny, 3M, and Michael Wedlake

5:00-9:00 pm – Offsite Dinner & Networking (Optional): Hosted at “The County Line”